

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S29	4709	((substrate wafer) with (chamber reactor)) with (reactant precursor)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/06/06 14:13
S30	1316	S29 and (activated irradiation) with (reactant precursor)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/06/06 14:23
S31	381	S30 and (activated irradiation) with (ray infrared microwave)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/06/06 14:24
S32	240	S31 and (activated irradiation) with (temperature)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/06/06 14:24
S33	97	S32 and (activated irradiation) with (molecular)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/06/07 09:48
S34	1	10/814553	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/06/07 07:16
S35	4	"6576564"	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/06/07 09:48